

IN THE CLAIMS:

Please AMEND claims 37-39 and 42, as follows.

Please ADD new claim 45, as follows. Please note that all claims currently pending in this application are reproduced below for the Examiner's convenience.

1-36. (Canceled)

37. (Currently Amended) An exposure apparatus for performing exposure of a substrate to light via a pattern of a reticle, said apparatus comprising:

a reticle stage configured to hold the reticle and to move;

a substrate stage configured to hold the substrate and to move;

an interface configured to input information of a condition of the exposure; and

a controller configured to select an exposure method to be performed from a first exposure in which the exposure is performed while speeds of said reticle stage and said substrate stage are constant, and a second exposure method in which the exposure is performed while speeds of said reticle stage and said substrate stage are changing ~~determine whether the exposure is to be performed in at least one of an acceleration period, in which said reticle stage and said substrate stage are accelerated, and a deceleration period, in which said reticle stage and said substrate stage are decelerated,~~ based on the input information.

38. (Currently Amended) An apparatus according to claim 37, wherein the condition of the exposure includes at least one of a shot size, a shot layout of the exposure to be performed, an alignment measurement value ~~measure~~, a shot layout of the exposure having been performed, a

shot position, and an accuracy required with respect to moving said reticle stage and said substrate stage.

39. (Currently Amended) An apparatus according to claim 37 ~~38~~, wherein the condition of the exposure includes a synchronization accuracy with respect to moving said reticle stage and said substrate stage.

40. (Previously Presented) A method of manufacturing a device, said method comprising steps of:

performing exposure of a substrate to light via a pattern of a reticle using an exposure apparatus as defined in claim 37;

developing the exposed substrate; and

processing the developed substrate to manufacture the device.

41. (Previously Presented) An apparatus according to claim 37, wherein said controller is configured to perform the determination based on a user's indication if a manual specification mode is specified as a determination mode of said controller.

42. (Currently Amended) An exposure apparatus for performing exposure of a substrate to light via a pattern of a reticle, said apparatus comprising:

an interface configured to input information of a condition of the exposure; and

a controller configured to select, among a plurality of exposure methods, an exposure method to be used to which correction data ~~among a plurality of exposure methods so~~

~~that a measure~~, required for exposure of a substrate and [[,]] obtained with respect to a previous exposure of a substrate can be ~~is~~ diverted, based on the input information.

43. (Currently Amended) An apparatus according to claim 42, wherein the plurality of exposure methods includes at least one of a static exposure with the substrate standing still while the exposure is performed, a constant speed exposure with the substrate moving at a constant speed while the exposure is performed and a changing speed exposure with the substrate moving at a changing speed while the exposure is performed.

44. (Currently Amended) A method of manufacturing a device, said method comprising steps of:

performing exposure of a substrate to light via a pattern of a reticle using an exposure apparatus as defined in claim 42;

developing the exposed substrate; and

processing the developed substrate to manufacture the device.

45. (New) An apparatus according to claim 42, wherein the correction data is used for correcting a measurement value of a surface position of the substrate.